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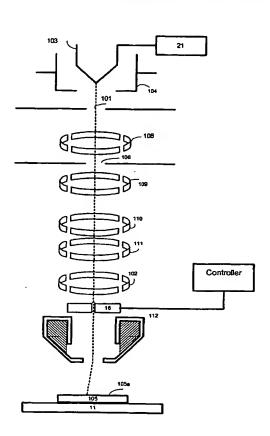
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(54) Title: A METHOD FOR MEASURING AND REDUCING ANGULAR DEVIATIONS OF A CHARGED PARTICLE BEAM



(57) Abstract: The invention provides a system and method for determining an angular deviation of a charged particle beam and for calibrating a charged particle beam system that are based upon multiple measurements of a test object that include sidewalls of high sidewall angle uniformity. A path of a charged particle beam is controlled by multiple beam control parameters. The method determines the parameters that will substantially reduce the angular deviation and applies them in order to calibrate a charged particle beam system.